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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF: :

Hiroshi IKEDA, et al. : GROUP ART UNIT: 1754

SERIAL NO.: 09/463,961 :

FILED: MAY 25, 2000 : EXAMINER: JOHNSON

FOR: PROCESS AND APPARATUS FOR TREATING SEMICONDUCTOR
PRODUCTION EXHAUST GASES

RECEIVED
APR 1 2003
TC 1700

RESPONSE TO RESTRICTION REQUIREMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

In response to the Official Action dated January 24, 2003, Applicants elect, with traverse, Group I, Claims 1-5, 7 and 9-10, for further prosecution.

REMARKS

The Office has required restriction in the present application as follows:

Group I: Claims 1-5, 7 and 9-10, drawn to a process for treating exhaust gases; and

Group II: Claim 8, drawn to an apparatus for treating exhaust gases.

Applicants elect, with traverse, Group I, Claims 1-5, 7 and 9-10, for further prosecution.

Applicants traverse the Restriction Requirement on the grounds that the Office has not applied the same standard of unity of invention as the International Preliminary Examination Authority. The Authority did not take the position that unity of invention was lacking in the International application and examined all claims together (see the